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| U.S. Department of Commerce, Patent and Trademark Office INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary) | Application No.: | Unknown |
| | Filing Date: | Unknown |
| | First Named Inventor: | Hamza Yilmaz |
| | Group Art Unit: | Unknown |
| | Examiner Name: | Unknown |
| | Confirmation No.: | Unknown |
| | Attorney Docket No.: | YMZ004 US |

| U.S. Patent Documents | | | | | | | |
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| *Examiner Initials | | Document Number | Date | Name | Class | Subclass | Filing Date if Appropriate |
| | 1. | 5,168,331 | 12/01/92 | Yilmaz | 257 | 331 | |
| | 2. | 5,216,275 | 06/01/93 | Chen | 257 | 493 | |
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| Foreign Patent Documents | | | | | | | |
| | | | | | | | Translation |
| | | Document | Date | Country | Class | Subclass | Yes No |
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| Other Art (Including Author, Title, Date, Pertinent Pages, Etc.) | | | | | | | |
| | 3. | Jongdae Kim et al., "High-Density Trench DMOSFETs Employing Two Step Trench Technique and Trench Contact Structure", ISPSD-2003 Proceedings, pp. 1-4 | | | | | |
| | 4. | Il-Yong Park et al., "Novel Process Techniques for Fabricating High Density Trench MOSFETs with Self-Aligned N ⁺ /P ⁺ Source Formed on the Trench Side Wall", ISPSD-2003 Proceedings, pp. 1-4. | | | | | |
| | 5. | M.A.A. In 'tZandt, et al., "Record-low 4mΩ mm ² specific on-resistance for 20V Trench MOSFETs", ISPSD-2003 Proceedings, pp. 1-4. | | | | | |
| | 6. | Mohamed Darwish et al., "A New Power W-Gated Trench MOSFET (WMOSFET) with High Switching Performance", ISPSD-2003 Proceedings, pp 1-4. | | | | | |
| | 7. | Syotaro Ono et al., "30V New Fine Trench MOSFET with Ultra Low On-Resistance", ISPSD-2003 Proceedings, pp. 1-4. | | | | | |
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| Examiner: | Date Considered: |
| * Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication with applicant. | |